

ABSTRACT OF THE DISCLOSURE

A projection system projects a pattern formed on a mask onto a photosensitive substrate. An illumination optical system forms an illumination field at a position on the mask. A drive relatively moves the mask and the photosensitive substrate with respect to the projection system along a predetermined scanning exposure direction. A first illumination adjustment mechanism adjusts an illumination characteristic along the scanning exposure direction. A second illumination adjustment mechanism adjusts an illumination characteristic in a direction crossing the scanning exposure direction. A first telecentricity adjustment mechanism applies an inclined component to telecentricity. A second telecentricity adjustment mechanism adjusts the telecentricity relative to the position of an optical axis.

00697639-102700